

Appl. No. 10/709,320
Amdt. Dated 11/03/2005
Reply to Office action of August 3, 2005

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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Confirmation No. 3319

In re : Application of Angyal, et al.
For : LOW-K INTERLEVEL DIELECTRIC LAYER (ILD) AND METHOD
Serial No. : 10/709,320
Filed : April 28, 2004
Group Art Unit : 2818
Examiner : Andy Huynh
Our Docket No. : FIS920040049US1
Customer No. : 24036

November 3, 2005

By Fax 571-273-8300
COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

This is in response to the Office Action dated August 3, 2005 having a shortened statutory period of response set to expire on November 3, 2005.

Please amend the referenced application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 7 of this paper.

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